

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
1	BRS	2351	etch\$3 with silicon adj oxide with plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/06 18:20			0
2	BRS	1	etch\$3 with silicon adj oxide with plasma and fluorine and bromine and iodiz\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/06 22:56			0
3	BRS	1	etch\$3 with silicon adj oxide with plasma and iodiz\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/06 18:25			0
4	BRS	32	etch\$3 with silicon adj oxide with plasma and fluorine and bromine and iodine	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/10 12:23			0
5	BRS	8	etch\$3 with silicon adj oxide with plasma with fluorine and (bromi\$2 or iodi\$2) with sidewalls	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/11 00:06			0
6	BRS	7	etch\$3 with silicon adj oxide with plasma with fluorine and (bromi\$2 or iodi\$2) and taper\$3 with sidewalls	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/11 14:44			0
7	IS&R	2	("6423644").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/11 00:38			0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
8	IS&R	2	("5644153").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/11 00:38			0
9	BRS	1	etch\$3 with silicon adj oxide with plasma with fluorine and (bromi\$2 or iodi\$2) and slop\$3 with sidewalls	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/11 14:48			0